

|                                   |  |                                       |   |             |
|-----------------------------------|--|---------------------------------------|---|-------------|
| <b>Notice of References Cited</b> |  | Application/Control No.<br>10/551,843 | Applicant(s)/Patent Under<br>Reexamination<br>OHMI ET AL. |             |
|                                   |  | Examiner<br>GRANT S. WITHERS          | Art Unit<br>2895  | Page 1 of 1 |

**U.S. PATENT DOCUMENTS**

| * | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Name           | Classification |
|---|--|-----------------|----------------|----------------|
| * | A US-5,876,788 A                                 | 03-1999         | Bronner et al. | 427/81         |
| * | B US-6,291,866 B1                                | 09-2001         | Wallace et al. | 257/410        |
| C | US-  |                 |                |                |
| D | US-  |                 |                |                |
| E | US-  |                 |                |                |
| F | US-  |                 |                |                |
| G | US-  |                 |                |                |
| H | US-  |                 |                |                |
| I | US-  |                 |                |                |
| J | US-  |                 |                |                |
| K | US-  |                 |                |                |
| L | US-  |                 |                |                |
| M | US-  |                 |                |                |

**FOREIGN PATENT DOCUMENTS**

| * | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Country | Name | Classification |
|---|--|-----------------|---------|------|----------------|
| N |  |                 |         |      |                |
| O |  |                 |         |      |                |
| P |  |                 |         |      |                |
| Q |  |                 |         |      |                |
| R |  |                 |         |      |                |
| S |  |                 |         |      |                |
| T |  |                 |         |      |                |

**NON-PATENT DOCUMENTS**

| * | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)                                       |
|---|---|
| U | Visokay, M. R. "Application of HfSiON as a gate dielectric material" App. Phys. Letters Vol. 80 Num 17 04/29/2002 pp. 3183-3185 |
| V |   |
| W |   |
| X |   |

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.